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Compact Model for Multiple Independent Gates Ambipolar Devices

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**Motivation:** Ambipolarity is often suppressed by processing steps; It can be exploited to enhance logic functionality Natural evolution of FinFE **Novel approach is needed to takle complex structures**

#### **Multiple Gates vs Multi-Gates**

In this context, Multiple Gates  $\neq$  Multi-Gate

GAA are Multi-Gate devices, but do not necessarily feature MultipleGates

Present work is about Multiple Independent Multi-Gate devices

Nanoarray-based structures can benefit, as well, of this approach

## **The approach: a collective strategy.**

Device is seen as composed by a series of Sections. How to **decompose** it:

Define appropriate sections  $(S_i)$  in the overallstructure.

 Hypothesis: no voltage drop at  $S_i$  and  $S_{(i+1)}$  contacts

Sections need not feature the same parameter set

The study of the complete device is reduced to the study of simpler parts

# **Current in sections**

 $\vert$   $\vert$ <sub>di</sub> can be calculated independently in each Section S<sub>i</sub>, provided we know  $V_{Di}$  and  $V_{Si}$  of all sections  $V_{Di}$  =  $Vs_{(i+1)}$   $Id_{Si} = Ids_{(i+1)}$ 

#### **Device section modeling**

**Idea:** to study such devices with these free parameters:

**L1, L2, L3** (different length of the sections) **VG1, VG2, VG3** (different applied voltages to the gates)

**R** (radius of the nanowire) **tox** (oxide thickness) **Idi** independently calculated in sections S<sub>i</sub> exploiting a charge-based model



pote



**Arbitrary Num. of gates**  $V_{Gi} - \Delta \varphi - V_{Pi} - \frac{kT}{q} \log \left( \frac{8}{\delta R^2} \right) = \frac{Q_{si0}}{C_{ox}} + \frac{kT}{q} \log \left( \frac{Q_{si0}}{Q_0} \right) + \frac{kT}{q} \log \left( \frac{Q_{si0} + Q_0}{Q_0} \right)$ Qsi0 can be



# **Extensions**

Same nature of the problem, same approach, slight modifications

# **Validation**

Theoretical: numerical simulations TCAD (Silvaco Atlas)

Experimental: at this stage of development, we still did not perform this kind of verification





## **Results: triple section, one gateless**



# **Conclusions**

**Fast (second vs. hours) and accurate (max err negligible) simulation**



# **Compact Model for Multiple Independent Gates Ambipolar Devices**



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**Charge-based model** is used at Single Section level to obtain current information .Drain current calculated as:



 $V_{pi}$  obtained through the charge control equation:

**Gateless section**

 $Q^* = Q - \alpha$ 



**Doped** 





 $\sum_{i=1}^{n}$   $I_{DS_i}$   $i = 2,...,n$   $\frac{1}{2C_{OX}L_i}Q_{si0}^2 + \frac{2V_{th}}{L_i}Q_{si0} - \frac{Q_{s1}^2}{2C_{OX}L_1} - \frac{2V_{th}Q_{s1}}{L_1} = 0$ 

$$
\delta^* = \frac{e^{\alpha/(C_{ox}Vt)}}{N_A/n_i} \quad V_{GS} - \Delta\varphi - V - \frac{kT}{q} \log\left(\frac{8e^{\alpha/(VtC_{ox})}}{\delta\frac{N_A}{n_i}R^2}\right) = \frac{Q - \alpha}{C_{ox}} + \frac{kT}{q} \log\left(\frac{Q - \alpha}{Q_0}\right) + \frac{kT}{q} \log\left(\frac{Q - \alpha}{Q_0}\right)
$$

determined as positive root of:

